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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		APPLICANT Takako YAMAGUCHI et al.				
LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)		FILING DATE April 1, 2005		GROUP Unassigned		
May 3, 2005						
U.S. PATENT DOCUMENTS						
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	US 6,171,730 B1	01/09/2001	Kuroda et al.	430	5	
	2001/0046719 A1	11/29/2001	Yamaguchi et al.	438	11	
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FOREIGN PATENT DOCUMENTS						
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	11-317345	11/16/1999	Japan			Abstract
	WO 03/001869 A2	01/09/2003	PCT			
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)						
	International Search Report mailed September 27, 2004, issued in corresponding International Application No. PCT/JP2004/09375.					
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	McNab, S. J., et al., "Analytic study of gratings patterned by evanescent near field optical lithography," J. Vac. Sci. Technol. B 18(6), Nov/Dec 2000, pp. 2900-2904.					
	Luo, Xiangang, et al., "Surface plasmon resonant interference nanolithography technique," Applied Physics Letters, Vol. 84, No. 23, June 7, 2004, pp. 4780-4782.					
	Alkaisi, Maan M., et al., "Nanolithography in the Evanescent Near Field," Advanced Materials, 13, No. 12-13, July 4, 2001, pp. 877-887.					
EXAMINER Jonathan Jelsma/			DATE CONSIDERED 08/19/2008			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609, Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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